Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2	array and electrodes same mask and synthesis and (angle near3 opening) with mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/05 14:09
L2	14	array and electrodes same mask and (angle near3 opening) with mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/05 14:12
L3	102	Silicon same mask and (angle near3 opening) with mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/05 14:13
L4	75	Silicon with mask and (angle near3 opening) with mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/05 14:13
L5	36	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (stainless with holder) with electrode	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/05 16:05
S1	14	("4956067" "5985356" "6045671" " 6187164" "6364956" "6455316" "64 68806").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/27 14:20
S2	19	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (parallel with (synthesis)) same array	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON · ,	2006/12/27 16:40
S3	101	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (parallel with (material)) same array	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/27 16:40

S4	83	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (parallel with (material)) same array and electrodes	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 11:49
S5	203	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (parallel) same array and electrodes and synthesis	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 11:56
S6	203	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (parallel) same array and electrodes and synthesis	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 13:24
S7	· 51	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (parallel) same array and electrodes same mask and synthesis	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 16:52
S8	86	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (electrode) same array and electrodes same mask and synthesis	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 14:45
S9	314	(electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (electrode) same array and electrodes same mask and synthesis not S8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 14:46
S10	1	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (parallel) same array and electrodes same mask and synthesis and stainless with mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 16:59
S11	20	(electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (parallel) same array and electrodes same mask and synthesis and stainless with mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 16:57

S12	1	(parallel) same array and electrodes	US-PGPUB;	OR	ON	2007/01/03 16:58
JIL		same mask and synthesis and stainless with mask not S11	USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OK .	ON	2007/01/03 10.38
S13		("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (parallel) same array and electrodes same mask and synthesis and polymer with mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 17:01
S14	1	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (parallel) same array and electrodes same mask and synthesis and (taper\$3 near3 opening) with mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/04 12:01
S15	1	("205"/\$.ccls. "204"/\$.ccls.) and (electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and array and electrodes same mask and synthesis and (taper\$3 near3 opening) with mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/05 14:33
S16 ⁻	4	(electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and array and electrodes same mask and synthesis and (taper\$3 near3 opening) with mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 17:27
S17	4	array and electrodes same mask and synthesis and (taper\$3 near3 opening) with mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/05 14:09
S18	65	(electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (taper\$3 near3 opening) with mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 17:34
S19 ⁻	251	(taper\$3 near3 opening) with mask not S18	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/04 14:50

S21	15	((taper\$3 near3 opening) with mask) and steel with mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/03 17:44
S22	6	("204"/280.ccls.) and array and electrodes same mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/04 13:26
S23	6	("204"/280.ccls.) and array and electrodes same mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/04 13:44
S24	24	("204"/280-297.01.ccls.) and array and electrodes same mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/04 13:59
S25	370	("204"/280-297.01.ccls.) and array and electrodes	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/04 13:59
S26	346	("204"/280-297.01.ccls.) and array and electrodes not S24	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON _.	2007/01/04 13:59
S27	. 4	("204"/280-297.01.ccls.) and array and electrodes and mask with plate not S24	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/04 14:02
S28		("204"/280-297.01.ccls.) and array same electrodes and mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2007/01/04 14:03

S29	7	("204"/280.ccls.) and array same electrodes and mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/04 14:07
S30	37	("204"/280,286.1,411-412.ccls.) and array same electrodes and mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2007/01/04 15:19
Ş31	65	(electrolysis electrolytic electrochemic\$4 plating electrodeposit\$5 electroplat\$5) and (taper\$3 near3 opening) with mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2007/01/04 14:40
S32	6	((taper\$3 near3 opening) with mask) and steel with mask not S31	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/04 14:40
S33	126	(taper\$3 near3 opening) with mask and electrode	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2007/01/04 14:50
S34	7	("204"/280,286.1,411-412.ccls.) and array same electrodes and rotating near3 disk	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/04 15:21
S35	47	("204"/\$.ccls.) and array same electrodes and rotating near3 disk	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON ·	2007/01/04 15:24
S36	182	("204"/\$.ccls.) and (rotating near3 disk) with electrode	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/04 15:24

		T	T	I		1
S37	38	("204"/\$.ccls.) and array same electrodes and (rotating near3 disk) with electrode	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/04 15:46
S38	2	("4911794" "6827839").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2007/01/04 15:32
S39	85	array same electrodes and (rotating near3 disk) with electrode not S37	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/04 15:35
S40	74	("204"/\$.ccls.) and array same electrodes and (rotating near3 electrode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/04 15:46
S41	74	("204"/\$.ccls.) and array same electrodes and (rotating near3 electrode) not S39	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/04 15:57
.S42	47	("204"/\$.ccls.) and array same electrodes and (rotating near3 disk)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/04 15:57
S43	4	"6969451".pn. "5120421".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/05 10:56
S56	2	\$3"0062047" and array	EPO; DERWENT; IBM_TDB	OR	ON	2007/01/05 10:54
S58	2	\$4"0040868" and electrochemical	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/05 10:56